Technical Data Sheet

PLATE PROCESSOR CLEANER

Plate Processor Bath Cleaner, for CTP and conventional offset plate processors

Application advice for best performance;

- Processor Cleaner can be used pure or mixed with water (up to 1 +6) depending on the degree of soiling.
- Empty the processor line (Developer).
- Do not change filter at this stage.
- Fill Processor Cleaner (mixed with water) into the processor and let it work for approx.15 minutes. The processor must run by normal developer temperature
- Drain the cleaning solution and rinse again several times with water.
- Replace filter, refill bath with fresh developer.
- **Manual use:** apply Processor Cleaner as concentrate or up to 1+1 mixed with water with a brush on the area to be cleaned, let the cleaner work a few minutes and then remove with a wet sponge.

Key Features;

- Removes plate coating and as well other build-ups residues in the plate processor.
- Very strong, powerful cleaner.
- No swelling of rollers or component attack.
- Content corrosion inhibitor.
- Can be used for CTP, CtcP and conventional offset plate processors and for photopolymer plate processor as well.
- Very cost effective.